

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					98-0001-1		09/518,970 10649186	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Tom A. Watson et al.			
					Filing Date		Group	
					March 6, 2001 8-26-03		1762 2828	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AL	AA	4,890,294	12/26/89	Nishimae et al.	372	57	/	
AL	AB	5,009,963	04/23/91	Ohmi et al.	428	472.2		
AL	AC	5,897,847	04/27/99	Jursich et al.	423	219		
AL	AD	6,024,885	02/15/00	Pendharkar et al.	216	22		
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	AL							
	AM							
	AN							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
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	AP							
	AQ							
	AR							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
/	AS							
	AT							
	AU							
Examiner AL		Date Considered 3-3-05						
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>								

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Tom A. Watson et al.			
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					8-26-2003		2828 Unknown	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AR	AA	5,047,115	09/10/1991	Charlet et al.	156	643		
AL	AB	5,444,259	08/22/1995	Ohmi	250	452.21		
AL	AC	5,360,768	11/01/1994	Ohmi et al.	437	238		
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Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
AL	AL	EP 0794 598 A1	10/09/1997	Europe				
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	AO							
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
AR	AQ	Ultra Clean Manufacturing Technology Co., Ltd., "CRP & FP - Gas Supply System for the Next Generation of ULSI," (Undated) 16 pages						
AL	AR	N. Miki et al., "Vapor-Liquid Equilibrium of the Binary System HF-H ₂ O Extending to Extremely Anhydrous Hydrogen Fluoride," (March 1990) J. Electrochem. Soc., Vol. 137, No. 3, ©The Electrochemical Society, Inc., pages 787 - 790						
AL	AS	N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869						
Examiner		H. Rodriguez						
		Date Considered		3-3-05				
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AR	AR	Phil Danielson, "Gas Loads From Elastomer Seals," (January 1999) Vacuum & Thinfilm, pages 14 - 15						
AR	AS	STELLA CHEMIFA Corporation, "Fluorine Passivation Technology," (1998) 11 pages						
Examiner		Armando Rodriguez		Date Considered		3-3-05		
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							Translation
		Document	Date	Country	Class	Subclass	Yes No
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
AR	AQ	N. Maki et al., "Fluorine Passivation of Metal Surface for Self-Cleaning Semiconductor Equipment," (February 1990) IEEE Transactions on Semiconductor Manufacturing, Vol. 3, No. 1, pages 1 - 11					
AR	AR	M. Maeno et al., "Optimization of Fluorine Passivation of Stainless Steel Surfaces," (May 1992) IEEE Transactions on Semiconductor Manufacturing, Vol. 5, No. 2 pages 107 - 113					
AS	AS	Hashimoto Chemical Corporation, "Fluorine Passivation Technology," (1997) pages 1 - 11					
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				M-7697 US		10644166		
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(Use several sheets if necessary)				Tom A. Watson et al.				
				Filing Date		Group		
				8-26-03		2826 Unknown		
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
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Foreign Patent Documents								
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AQ	M. Maeno et al., "Fluorine-Passivated Electroless Ni-P Films," (October 1994) J. Electrochem. Soc., Vol. 141, No. 10, ©The Electrochemical Society, Inc., pages 2649 - 2654						
	AR	G.M. Jurisch et al., "Gas Contaminant Effects in Discharge-Excited KrF Lasers," (April 20, 1992) Applied Optics, Vol. 31, No. 12, pages 1974 - 1981						
	AS	W. Holber et al., "Reducing PFC Emissions From CVD Reactors," (March 1999) Vacuum & Thinfil, pages 26 - 29						
Examiner		Date Considered 3-3-05						
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant(s) Tom A. Watson et al.	
	Filing Date 8-26-03	Group 2828
		Unknown

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Foreign Patent Documents

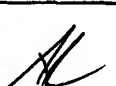


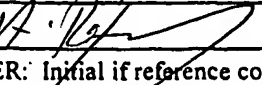
		Document	Date	Country	Class	Subclass	Translation	
							Yes	No
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AL	AQ	Future Fab International, "XPS Analysis on Fluorine Removal by Plasma Cleaning," (Undated) pages 289 - 293
AL	AR	P.M. Clarke et al., "Gas-Phase Interactions Between WF ₆ and Metal Surfaces," (1994) Conference Proceedings ULSI-IX - Materials Research Society, pages 411 - 417; 59 68
AL	AS	Y. Shirai et al., "Fluorine Passivation of Metal Surface," (1996) CleanRooms "'96 West Session 602, pages 68 - 71

Examiner *Armando Rodriguez* Date Considered 3-3-05

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(Use several sheets if necessary)				Tom A. Watson et al.			
				Filing Date		Group 2828	
				8-26-03		Unknown	
U.S. Patent Documents							
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							Translation
		Document	Date	Country	Class	Subclass	Yes No
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	AQ	Phil Danileson, "Rate-of-rise Measurements," (November/December 1998) Vacuum & Thinfil, pages 12 - 13					
	AR	Vacuum & Thinfil, "The Evolution of RF," (November/December 1998) pages 30 - 33					
	AS	Y. Minamitani et al., "Characteristics of A Corona Reactor As A Gas Purifier For Excimer Lasers," (Undated) pages 1 - 18					
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
AL	AQ	H.E. Litvak, "End Point Control Via Optical Emission Spectroscopy," (1996) J. Vac. Sci. Technol. B14(1), pages 516 - 520							
AL	AR	D.W. Greve et al., "Process Control Based On Quadrupole Mass Spectrometry," (1996) J. Vac. Sci. Technol. B14(1), pages 489 - 493							
AL	AS	Los Alamos National Laboratory, "Excimer Laser Chemical Problems," (1985) U.S. Dept. of Commerce, 81 pages							
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		Document	Date	Country	Class	Subclass	Yes	No
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	AM							
	AN							
	AO							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AL	AP	Kazuhide Ino et al., "Plasma Enhanced <i>In Situ</i> Chamber Cleaning Evaluated by Extracted-Plasma-Parameter Analysis," (1996) IEEE Transaction on Semiconductor Manufacturing, Vol. 9, No. 2, pages 230 - 240
AL	AQ	Kenji Komine et al., "Residuals Caused by The CF ₄ Gas Plasma Etching Process," (May 1996) Jpn. J. Appl. Phys. Vol. 35, pages 3010 - 3014
AL	AR	A.L. Cabrera et al., "Surface Analysis Of Copper, Brass, and Steel Foils Exposed to Fluorine Containing Atmospheres," (1990) J. Vac. Sci. Technol. A8, pages 3988 - 3996
AL	AS	I. Kazuhide et al., " <i>In Situ</i> Chamber Cleaning Using Halogenated-Gas Plasmas Evaluated by Plasma-Parameter Extraction," (January 1994) Jpn. J. Appl. Phys. Vol. 33, pages 505 - 509

Examiner A. [Signature] Date Considered 3-3-05

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